



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Keith J. Machia, et al.

Examiner: Hung Nguyen

Serial No.: 10/691,729

Art Unit: 2851

Filed: October 23, 2003

Docket: BUR920010164US2 (15016A)

For: METHOD OF PHOTOLITHOGRAPHIC
EXPOSURE DOSE CONTROL AS A
FUNCTION OF RESIST SENSITIVITY

Confirmation No.: 7980

Date: August 19, 2004

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT UNDER 37 CFR 1.111

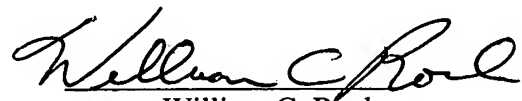
Sir:

Responsive to the Office Action dated April 19, 2004, please amend this patent application as follows.

CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents, P. O. Box 1450, Alexandria, VA 22313-1450 on August 19, 2004.

Dated: August 19, 2004


William C. Roch